

**Amendments to the Claims:**

Please amend claims 2-9, 11-20, 47-52, and 54-61 as set forth below. Please cancel claims 1, 10, 46, and 53. Following is a complete listing of the claims pending in the application, as amended:

1. (Cancelled)

2. (Currently amended) The method of claim 87 ~~4~~ wherein the radiation includes a beam having a beam width at the microlithographic substrate, and wherein moving the microlithographic substrate includes oscillating the microlithographic substrate toward and away from the reticle along an axis generally parallel to the substrate radiation path segment, further wherein a motion of the microlithographic substrate is periodic and wherein moving the microlithographic substrate includes moving the microlithographic substrate for one period during the time the microlithographic substrate moves transverse to the beam by a distance of one beam width or about one beam width.

3. (Currently amended) The method of claim 87 ~~4~~ wherein the radiation includes a beam having a beam width at least proximate to an intersection between the beam and the microlithographic substrate, and wherein moving the microlithographic substrate includes oscillating the microlithographic substrate toward and away from the reticle along an axis generally parallel to the substrate radiation path segment, further wherein a motion of the microlithographic substrate is periodic and wherein moving the microlithographic substrate includes moving the microlithographic substrate for an integer number of periods during the time the microlithographic substrate moves transverse to the beam by a distance of one beam width or about one beam width.

4. (Currently amended) The method of claim 87 ~~4~~ wherein moving the reticle includes moving the reticle along a reticle path generally normal to the reticle radiation path segment at least proximate to a point where the radiation impinges on the reticle.